Investigation of the work function fluctuations for high precision experiments

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Why?

In high precision experiments the electric potentials have to be known precisely! *a*SPECT 10 mV | KATRIN 20 mV Electrodes, defining the potentials for charged particles, can show spatial fluctuations of the work function up to several 100 mV!

Systematic investigations

Observation of the patch effect

Electroplating

... leads to areas with different crystal orientations of Au. The work function depends on the crystal orientation. This

orientation	phi /eV
Au(100)	5.31
Au(110)	5.41
Au(111)	5.47
Au(110) Au(111)	5.41 5.47

E.g. the crystal orientations of gold lead to 160 mV pk-pk difference!

What's the problem?

Spatial work function fluctuations $\Phi(\vec{x})$ corresponds to local Fermi levels $E_F(\vec{x})$. Due to balancing of electrically connected Fermi levels, there will be a shift of the vacuum level by the **contact potential difference**

 $\phi_{\rm CPD} = \Phi(\vec{x}_f) - \Phi(\vec{x}_i)$



Effect of spatial work function fluctuations.

A charged particle moving from \vec{x}_i to \vec{x}_f and thus $E_{\mathrm{F},i}$ to $E_{\mathrm{F},f}$. Balancing of the Fermi levels lead to an electric field, which shifts the final kinetic energy by $q\phi_{\mathrm{CPD}}$. In experiments utilizing an electrostatic filter like *a*SPECT and KATRIN (MAC-E type), this effect has to be taken into account.



How to measure? - Kelvin probe!

Simplified Kelvin probe circuit





Temporal stability of Au(111) on sapphire

... shows that the inital RMS fluctuation "out of box" can be nearly recovered by a vacuum cleaning procedure or/and a bake out.



Conclusion and Outlook

Studied and commissioned a scanning Kelvin probe system
 Now stable at 3 meV_{RMS}

Samples being investigated

Au electroplated on copper (aSPECT)
Au(111) epitaxially grown on sapphire
Au sputtered on silicium/beryllium, ...





 Electroplated samples >cm² are patched, thus show high meV_{RMS}, e.g. Au on silicon showed fluctuations down to 4.5 meV_{RMS}
 Further investigations:

Measure filter electrode and decay volume electrode used in aSPECT beamtime 2013 as input for simulations!

- Measure under beamtime conditions:
 - Influence of adsorbed layers on fluctuations
 Influence of cryogenic temperature
 - Therefore a UHV Kelvin probe will be commissioned!

The Mainz Kelvin probe is a reliable system to investigate work function fluctuations, which can cause systematic errors in your experiment! Check and ask for support! Christian Schmidt, chschmidt@uni-mainz.de

www.ag-heil.uni-mainz.de